

SOLAR NEW INLINE PLATFORM

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Highest reliability for PV mass production

The new RENA inline platform is designed for easy use and best performance for PV mass production. Intelligent features ensure reliable and stable process control and allow an easy process transfer from one tool to another. Optimised media handling and fluid dynamics reduce the costs of ownership and improve the process performance.

Areas of application

- New Inline platform for wet processing
- InTex – InPolish – InDop – InOx/InOxSide – InOx EB/InOxSide EB – InSiOx

Features and benefits

Gentle Transport System

- Roller system without side guides
- Gentle transport with solid rollers
- Open gear on front side
- Breakage rate < 0.05 % for 180 μ m wafer, with automation and μ -crack testing

Good Accessibility

- Fast exchange of transport rollers and spray bars
- Open gear on front side
- User friendly access to all components
- Semi-automatic sampling ports

Small Footprint

- Electrical cabinet, pump station and chiller integrated in the tool
- Fast tool start-up
- Total equipment depth only 2150 mm

Intelligent process control

- Relevant media settings via PLC
- Self calibrating dosing system with < 1% accuracy
- Media supply system and exhaust system insensitive to variation of facilities flow and pressure
- Easy process transfer tool to tool

Low Chemical Usage

- Optimised nozzles with smooth jet
- Multi stage rinse cascade
- DI water usage 320 ml/wafer
- Acid usage for texturing 9.5 ml/wafer
- Squeegee rollers after chemical processing

Smooth Drying

- AirChannelDryer with blower technology, without CDA usage

Homogeneous double side processing

- Optimised fluid mechanics

Efficient single side processing

- Homogeneous process results in one process step
- Patented process

User-friendly software

- Intuitive Operation
- Advanced data logging
- MES system (PPC, XML, SECS GEM)

Perfect match with RENA automation systems

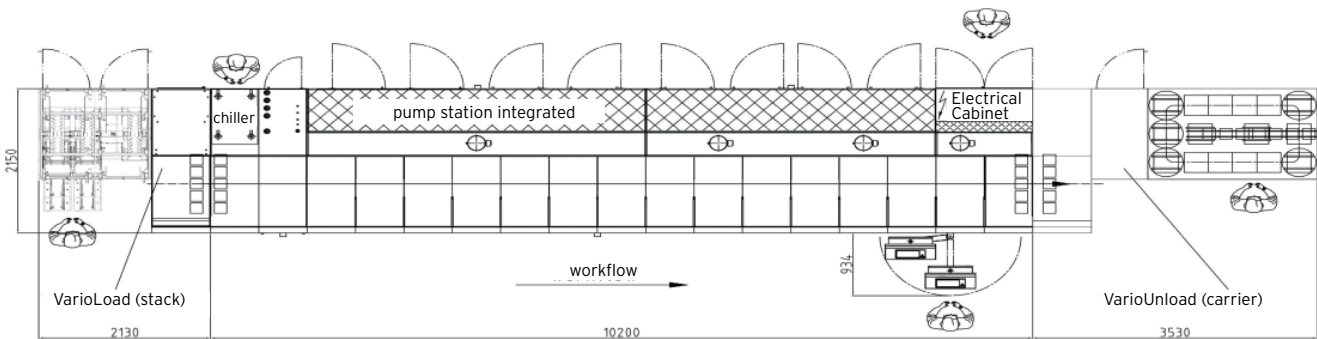
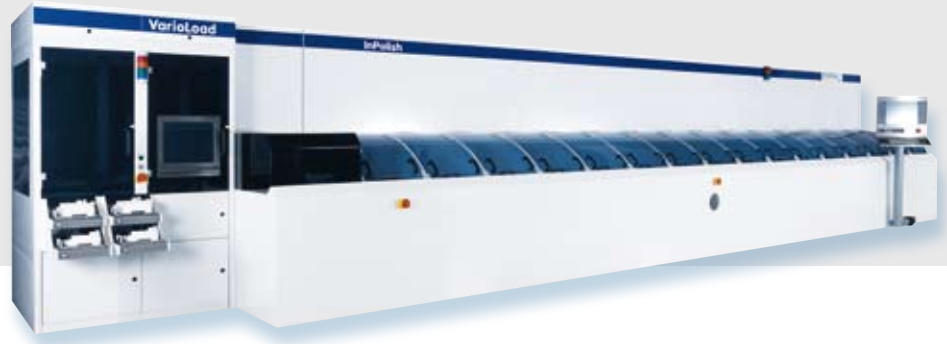




Spray nozzles



Open gear



Technical Data New Inline Platform

	InTex ST	InTex HT
Dimension examples	5 lanes for 156 mm 8400 x 2150 x 2350 mm (length x width x height)	5 lanes for 156 mm 10200 x 2150 x 2350 mm (length x width x height)
Throughput	1875 wafers/h gross	3000 wafers/h gross
Max. throughput / lane	375 wafers/h	600 wafers/h
Wafer thickness	> 150 µm	> 150 µm
Media consumption		
DI-water	320 ml/wafer	320 ml/wafer
Acid (for texturing)	9.5 ml/wafer	9.5 ml/wafer
Exhaust	2000 m³/h	2000 m³/h